

# INTERNATIONAL STANDARD

REDLINE VERSION

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**Measurement of quartz crystal unit parameters -  
Part 11: Standard method for the determination of the load resonance frequency  $f_L$  and the effective load capacitance  $C_{Leff}$  using automatic network analyzer techniques and error correction**

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## INTERNATIONAL ELECTROTECHNICAL COMMISSION

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## FOREWORD

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This redline version of the official IEC Standard allows the user to identify the changes made to the previous edition IEC 60444-11:2010. A vertical bar appears in the margin wherever a change has been made. Additions are in green text, deletions are in strikethrough red text.

IEC 60444-11 has been prepared by IEC technical committee 49: Piezoelectric, dielectric and electrostatic devices and associated materials for frequency control, selection and detection. It is an International Standard.

This second edition cancels and replaces the first edition published in 2010. This edition constitutes a technical revision.

This edition includes the following significant technical changes with respect to the previous edition:

- a) key content of withdrawn IEC TR 60444-4 is reproduced as Annex A;
- b) some formulae in the first edition have been corrected.

The text of this International Standard is based on the following documents:

Draft	Report on voting
49/1489/CDV	49/1515/RVC

Full information on the voting for its approval can be found in the report on voting indicated in the above table.

The language used for the development of this International Standard is English.

This document was drafted in accordance with ISO/IEC Directives, Part 2, and developed in accordance with ISO/IEC Directives, Part 1 and ISO/IEC Directives, IEC Supplement, available at [www.iec.ch/members\\_experts/refdocs](http://www.iec.ch/members_experts/refdocs). The main document types developed by IEC are described in greater detail at [www.iec.ch/publications](http://www.iec.ch/publications).

A list of all parts in the IEC 60444 series, published under the general title *Measurement of quartz crystal unit parameters*, can be found on the IEC website.

The committee has decided that the contents of this document will remain unchanged until the stability date indicated on the IEC website under [webstore.iec.ch](http://webstore.iec.ch) in the data related to the specific document. At this date, the document will be

- reconfirmed,
- withdrawn, or
- revised.

## INTRODUCTION

This part of IEC 60444 defines the measuring method of load resonance frequency  $f_L$  using automatic network analyzer techniques.

At the same time, even though IEC TR 60444-4 [8]<sup>1</sup> specifying the manual measuring method has been withdrawn, the main contents of the manual measuring method remain as Annex A for the user's convenience. However, in case of dispute, the standard method as described below should be used as reference.

The figure of merit  $M$ , according to IEC 60122-1:2002, Table 1, is expressed in the following formula:

$$M = \frac{Q}{r} = \frac{1}{\omega C_0 R_1} \quad (1)$$

This gives good results in a frequency range up to 200 MHz. This method allows the calculation of load resonance frequency offset  $\Delta f_L$ , frequency pulling range  $\Delta f_{L1}$ ,  $\Delta f_{L2}$  and pulling sensitivity  $S$  as described in IEC 60122-1:2002, 2.2.31. ~~In contrary to the simple method of IEC 60444-4,~~ This measurement technique avoids the use of physical load capacitors, and allows higher accuracy, better reproducibility and correlation to the application. It extends the upper frequency limit from 30 MHz by the manual method ~~of IEC 60444-4~~ to 200 MHz approximately. This method is based on the error-corrected measurement technique of IEC 60444-5:1995 [9] and therefore allows the measurement of  $f_L$  and  $C_{Leff}$  together with the determination of the equivalent crystal parameters in one sequence without changing the test fixture.

With this method the frequency  $f_L$  is searched where the reactance  $X_C$  of the crystal has the opposite value of the reactance of the load capacitance.

$$X_C = -X_{CL} = \frac{1}{\omega_L C_L} \quad (2)$$

Furthermore, this method allows to determine the effective load capacitance  $C_{Leff}$  at the nominal frequency  $f_{nom}$ .

<sup>1</sup> Numbers in square brackets refer to the Bibliography.

## 1 Scope

This part of IEC 60444 defines the standard method of measuring load resonance frequency  $f_L$  at the nominal value of  $C_L$ , and the determination of the effective load capacitance  $C_{Leff}$  at the nominal frequency for crystals with the figure of merit  $M > 4$ .

## 2 Normative references

The following documents are referred to in the text in such a way that some or all of their content constitutes requirements of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

IEC 60122-1:2002, *Quartz crystal units of assessed quality - Part 1: Generic specification*  
IEC 60122-1:2002/AMD1:2017

IEC 60444-1:1986, *Measurement of quartz crystal unit parameters by zero phase technique in a pi-network - Part 1: Basic method for the measurement of resonance frequency and resonance resistance of quartz crystal units by zero phase technique in a pi-network*  
IEC 60444-1:1986/AMD1:1999

~~IEC/TR 60444-4, Measurement of quartz crystal unit parameters by zero phase technique in a  $\pi$ -network — Part 4: method for the measurement of the load resonance frequency  $f_L$ , load resonance resistance  $R_L$  and the calculation of other derived values of quartz crystal units, up to 30 MHz~~

~~IEC 60444-5:1995, Measurement of quartz crystal units parameters — Part 5: Methods for the determination of equivalent electrical parameters using automatic network analyzer techniques and error correction~~

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- [4] LEE, Arthur and CHAN, K., *Direct Impedance Method for Load Resonant Measurement of Crystals*; Proc. 21<sup>st</sup> Piezoelectric Devices Conference & Exhibition, 1999
- [5] VAN HERWIJNEN, M. and SOHRE, Frieder K.C., *Load-Resonance Measurement Accuracy of Ceramic Surface Mount Quartz Crystals*, Proc. 14<sup>th</sup> European Frequency and Time Forum (EFTF), 2002
- [6] IEC 60122-2, *Quartz crystal units for frequency control and selection - Part 2: Guide to the use of quartz crystal units for frequency control and selection*
- [7] IEC 60444-2, *Measurement of quartz crystal unit parameters by zero phase technique in a pi-network - Part 2: Phase offset method for measurement of motional capacitance of quartz crystal units*
- [8] IEC TR 60444-4:1998<sup>2</sup>, *Measurement of quartz crystal unit parameters by zero phase technique in a  $\pi$ -network - Part 4: Method for the measurement of the load resonance frequency  $f_L$  load resonance resistance  $R_L$  and the calculation of other derived values of quartz crystal units, up to 30 MHz*
- [9] IEC 60444-5:1995, *Measurement of quartz crystal units parameters - Part 5: Methods for the determination of equivalent electrical parameters using automatic network analyzer techniques and error correction*

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<sup>2</sup> This publication has been withdrawn.